

| L Number | Hits | Search Text | DB | Time stamp |
|----------|------|--|---|------------------|
| 1 | 247 | (oxidi\$8 near3 heat\$3) and 219/200-553.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 15:13 |
| 2 | 189 | ((oxidi\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 15:14 |
| 3 | 133 | ((((oxidi\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3) and gas | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 15:15 |
| 4 | 5 | (((((oxidi\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3) and gas) and resistive near layer | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 15:26 |
| 5 | 118 | (((((oxidi\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3) and gas) and metal\$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 15:43 |
| 6 | 22 | (((((oxidi\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3) and gas) and resist\$4 near layer | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 15:27 |
| 7 | 20 | (((((oxidi\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3) and gas) and resist\$4 near layer) and metal\$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 15:27 |
| 8 | 68 | (((((oxidi\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3) and gas) and metal\$4 with layer | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 15:43 |
| 9 | 47 | (((((oxidi\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3) and gas) and metal\$4 near2 layer | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 15:55 |
| 10 | 20 | (((((oxidi\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3) and gas) and metal\$4) and resist\$6 near2 control\$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 16:04 |
| 11 | 1 | (((((oxidi\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3) and gas) and reaction near2 product | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 16:04 |
| 12 | 1 | ((((oxidi\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3) and reaction near2 product | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 16:04 |

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| 13 | 25 | (((oxidiz\$8 near3 heat\$3) and 219/200-553.ccls.) and resist\$3) and resist\$6 near2 control\$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/14 16:05 |
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